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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/706,755	11/12/2003	Sung-Min Kim	5649-1147	7540
75	90 08/10/2005		EXAMINER	
Robert N. Cro	use		SMOOT, ST	TEPHEN W
Myers Bigel Sib	oley & Sajovec, P.A.		ART UNIT	PAPER NUMBER
P.O. Box 37428			AKI UNII	PAPER NOMBER
Raleigh, NC 27627			2813	
			DATE MAILED: 08/10/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	
	10/706,755	KIM ET AL.	
Office Action Summary	Examiner	Art Unit	- <del></del>
	Stephen W. Smoot	2813	
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	correspondence address	
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a repl If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailin earned patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply be tin ly within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication D (35 U.S.C. § 133).	
Status			
1) Responsive to communication(s) filed on 02 J	une 2005.		
,	s action is non-final.		
3) Since this application is in condition for allowa closed in accordance with the practice under the second secon	nce except for formal matters, pro		
Disposition of Claims			
4) ☐ Claim(s) 1.3-5,7,8 and 22-30 is/are pending in 4a) Of the above claim(s) is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1.3-5,7,8,22-24 and 26-30 is/are reje 7) ☐ Claim(s) 25 is/are objected to. 8) ☐ Claim(s) are subject to restriction and/o	wn from consideration.		
Application Papers			
9) ☐ The specification is objected to by the Examine 10) ☑ The drawing(s) filed on 12 November 2003 is/a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) ☐ The oath or declaration is objected to by the Example 2003.	are: a)⊠ accepted or b)⊡ object drawing(s) be held in abeyance. Set tion is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d	).
Priority under 35 U.S.C. § 119			
a) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:  1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Burea * See the attached detailed Office action for a list	ts have been received. ts have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	ion No ed in this National Stage	
Attachment(s)  1) ☑ Notice of References Cited (PTO-892)	4) 🔲 Interview Summary	(PTO-413)	
Notice of References Cited (PTO-992)  Notice of Draftsperson's Patent Drawing Review (PTO-948)  Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  Paper No(s)/Mail Date	Paper No(s)/Mail Da		

#### **DETAILED ACTION**

This Office action is in response to applicant's amendment filed on 02 June 2005.

### Claim Objections

1. Claim 8 is objected to because of the following informality:

In claim 8, line 1, change the claim dependency from "claim 2" to --claim 1--because the original claim 2 has been cancelled and its contents have been incorporated into claim 1.

Appropriate correction is required.

## Claim Rejections - 35 USC § 112

2. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

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3. Claims 1, 3-5, 7-8, 27-30 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claim 1 recites the limitation "the inner side wall" in line 9.

There is insufficient antecedent basis for this limitation in claim 1.

Claims 3-5, 7-8 are rejected under 35 U.S.C. 112, second paragraph, because they depend on claim 1.

Claim 27 recites the limitation "the substrate" in line 5.

There is insufficient antecedent basis for this limitation in claim 27.

Claims 28-30 are rejected under 35 U.S.C. 112, second paragraph, because they depend on claim 27.

### Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

5. Claims 22-24, 27-29 are rejected under 35 U.S.C. 102(b) as being anticipated by Akbar (US 5,656,845).

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Referring to Fig. 1 and column 3, line 61 to column 4, line 43, Akbar discloses an n-channel EEPROM with the following structural features:

- A substrate that includes a silicon substrate (20) and an overlying oxide layer
   (22);
- An active layer of single crystal silicon (25) formed on the oxide layer (22);
- The single crystal silicon layer (25) can be epitaxially grown (see column 6, line
   66 to column 7, line 1);
- Field oxide rows (72, 74) to isolate adjacent memory cells formed in direct contact with the oxide layer (22) (also see column 5, lines 11-16);
- A plurality of gates (44, 55, 62) within a memory cell between adjacent field oxide rows (72, 74) and over the oxide layer (22); and
- Three heavily doped n-type layers (38, 40, 58) that extend through the entire thickness of the single crystal silicon layer (25) to the oxide layer (22).

These are all of the limitations set forth in claims 22-24, 27-29 of the applicant's invention.

6. Claims 22-24, 26-30 are rejected under 35 U.S.C. 102(b) as being anticipated by Zahurak et al. (US 2002/0160574 A1).

Referring to Fig. 2 and paragraphs [0022] to [0025], Zahurak et al. disclose an SOI device with the following structural features:

A substrate that includes a bulk substrate (15) and an overlying insulating layer
 (20) that can be silicon nitride or silicon oxynitride;

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- A semiconductor layer (30) that can be single crystal silicon formed on the insulating layer (20);
- The semiconductor layer (30) is divided into active area regions (34) by forming isolation regions (38) that are in direct contact with the insulating layer (20);
- A plurality of gate structures (45) formed within an active area region (34); and
- The active area regions (34) extend through the entire thickness of the semiconductor layer (30) to the insulating layer (20).

These are all of the structural limitations set forth in claims 22-24, 26-30 of the applicant's invention.

Regarding the epitaxial silicon limitations of claims 22-23, 27-28, these are process limitations and the patentability of product-by-process claims are based on the structure implied by the process steps (see MPEP section 2113). Regarding claims 22, 27, epitaxial silicon implies single crystal silicon and the burden shifts to the applicant to show otherwise. Further, regarding claims 23, 28, multiple layers of epitaxial silicon would not necessarily be distinguishable from a single layer of single crystal silicon because the multiple layers can have the exact same composition.

## Allowable Subject Matter

7. Claim 25 is objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form to include all of the limitations of the base claim and any intervening claims.

8. The following is a statement of reasons for the indication of allowable subject matter: Claim 25 would be allowable because the prior art of record does not teach or suggest, in combination with the other claim limitations, an integrated circuit structure that includes an isolation structure that electrically isolates an active region, the active region having a plurality of gates and having two insulation layers beneath the plurality of gates that extend between opposing portions of the isolation structure, wherein an epitaxial silicon layer extends from the active region through both insulation layers.

#### Response to Arguments

9. Applicant's arguments, see pages 8-9, filed 02 June 2005, with respect to claims 1, 3, 5, 7 have been fully considered and are persuasive. The prior art rejections of claims 1, 3, 5, 7 based wholly or partially on Park et al. (US 2002/0047158 A1) have been withdrawn.

#### Conclusion

10. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Kawanaka and Duvvury et al. teach SOI structures that include plural gates formed within an isolation region.

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11. Applicant's amendment necessitated the new grounds of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

12. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Stephen W. Smoot whose telephone number is 571-272-1698. The examiner can normally be reached on M-F (8:00 am to 4:30 pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr. can be reached on 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8000.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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